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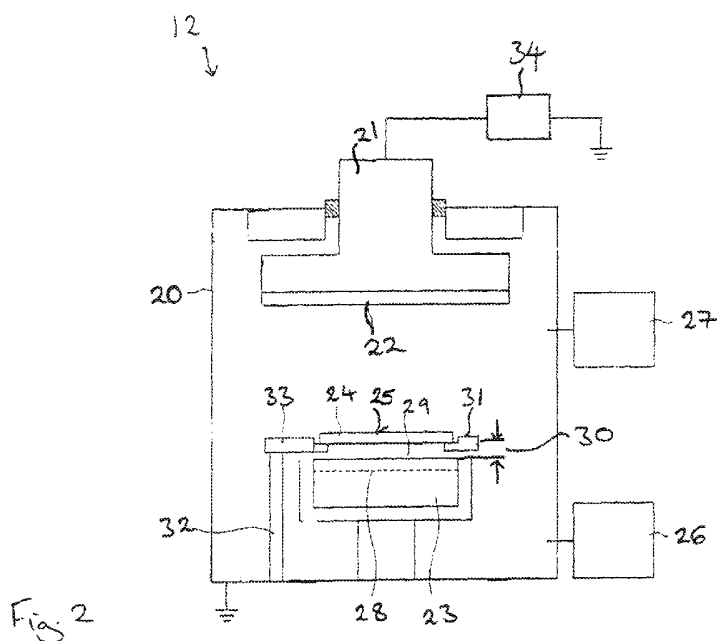
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(54) Title: METHOD FOR DEPOSITING AN ALUMINIUM NITRIDE LAYER



(57) Abstract: A method for depositing an aluminium nitride layer on a substrate is provided that comprises: providing a silicon substrate; placing the substrate in a vacuum chamber; conditioning a surface of the substrate by etching and providing a conditioned surface; depositing an aluminium film onto the conditioned surface of the substrate by a sputtering method under an atmosphere of argon and depositing an epitaxial aluminium nitride layer on the aluminium film by a sputtering method under an atmosphere of nitrogen and argon.